

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application Serial No. Unknown
 Filing Date Filed Herewith
 Inventor Weimin Li et al.
 Assignee Micron Technology, Inc.
 Group Art Unit Unknown
 Examiner Unknown
 Attorney Docket No. MI22-2274
 Customer No. 021567
 Title: Methods of Depositing Silicon Dioxide Comprising Layers in the
 Fabrication of Integrated Circuitry, Methods of Forming Trench Isolation,
 and Methods of Forming Arrays of Memory Cells

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References -- See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with
 37 CFR §1.56. Pursuant to 1276 OG 55, August 5, 2003, no copies of cited U.S.
 patents or U.S. patent application publications are included, as the date of filing
 of this patent application occurs after June 30, 2003. No admission is made
 regarding whether all the listed references are prior art.

Respectfully submitted,

Dated:

3-22-04

By:



Mark S. Matkin
 Reg. No. 32,268

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2274		SERIAL NO. Unknown	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Weimin Michael Li et al.			
				FILING DATE Filed Herewith		GROUP Unknown	

U.S. PATENT DOCUMENTS							
*Examiner's Initials	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	6,300,219 B1	10/09/01	Doan et al.			
	AB	6,534,395 B2	03/18/03	Werkhoven et al.			
	AC	10/615,051		Vaartstra (as filed)			07/07/2003
	AD	10/655,699		Derderian et al. (as filed)			09/05/2003
	AE						
	AF						
	AG						
	AH						
	AI						

FOREIGN PATENT DOCUMENTS							
Document Number	Date	Country	Class	Subclass	Translation		
					Yes	No	
AJ	WO 02/27063 A2	04.04.02	WIPO (Harvard College)				
AK							
AL							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
	AM		Hausmann et al., <i>Rapid Vapor Deposition of Highly Conformal Silica Nanolaminates</i> , 298 SCIENCE 402-406
			(October 11, 2002)
	AN		Klaus et al., <i>Atomic Layer Deposition of SiO₂ Using Catalyzed and Uncatalyzed Self-Limiting Surface Reactions</i> , 6 SURFACE REVIEW AND LETTERS, Nos. 3 and 4, pp. 435-448 (1999).
	AO		Miller et al., <i>Self-limiting chemical vapor deposition of an ultra-thin silicon oxide film using tri-(tert-butoxy) Silanol</i> , 397 THIN SOLID FILMS 78-82 (2001).
EXAMINER		DATE CONSIDERED	

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2274	SERIAL NO. Unknown
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Weimin Michael Li et al..	
				FILING DATE Filed Herewith	GROUP Unknown

U.S. PATENT DOCUMENTS							
*Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						

FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AJ							
	AK							
	AL							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
	AM		Hausmann et al., "Catalytic vapor deposition of highly conformal silica nanolaminates", Department of Chemistry and Chemical Biology, Harvard University, May 14, 2002, pp. 1-13.
	AN		
	AO		
EXAMINER		DATE CONSIDERED	

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.